

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:	)	PATENT APPLICATION
Inventor: Yoshi Ono	)	
Serial No.: Not Yet Assigned	)	Attorney Docket No.
Filed: Herewith	)	SLA 0669
Title: LOW TEMPERATURE NITRIDATION OF SILICON	)	

Honorable Commissioner for Patents  
Washington, D.C. 20231

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97**

Sir:

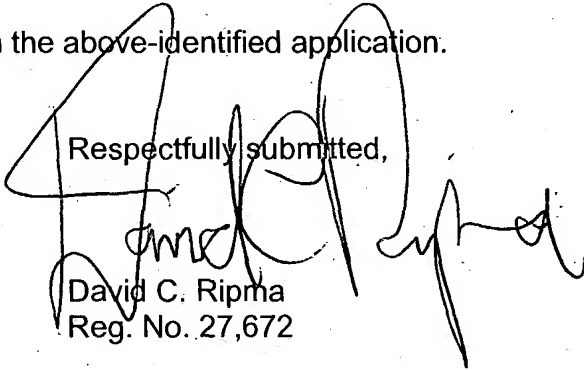
Listed on attached Form PTO-1449 is information submitted pursuant to  
37 C.F.R. §1.56. A copy of each listed publication is submitted herewith.

Applicant respectfully requests that the listed information be considered by  
the Examiner and made of record in the above-identified application.

(Date)

6/23/03

Respectfully submitted,

  
David C. Ripma  
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1449A/PTO Rev. 10/95		U.S. Department of Commerce Patent and Trademark Office		Complete If Known	
<b>LIST OF PRIOR ART CITED BY APPLICANT</b>  (use as many sheets as necessary)				Application Number	
				Filing Date	06-23-03
				First Named Inventor	Yoshi Ono
				Group Art Unit	
				Examiner Name	
Sheet	1	of	1	Attorney Docket No.	SLA.0669

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No. <sup>1</sup>	U.S. Patent Document Kind Number Code <sup>2</sup> (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear
		6,274,510 B1	Wilk et al.	08-14-01	

FOREIGN PATENT DOCUMENTS								
Examiner Initials	Cite No. <sup>1</sup>	Foreign Patent Document			Name of Patentee or Applicant of Cited Document.	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear	T <sup>6</sup>
		Office <sup>3</sup> Code <sup>5</sup>	Number <sup>4</sup>	Kind				

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T <sup>2</sup>
		K. Watanabe <i>et al.</i> , <i>Controlling the concentration and position of nitrogen in ultrathin oxynitride films formed by using oxygen and nitrogen radicals</i> , Appl. Phys. Lett. 76, 2940 (2000).	
		J. Joseph <i>et al.</i> , <i>A kinetics study of the electron cyclotron resonance plasma oxidation of silicon</i> , J. Vac. Sci. Technol. B10, 611 (1992).	

Examiner Signature		Date Considered	
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Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.  
<sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.1<sup>6</sup> if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached